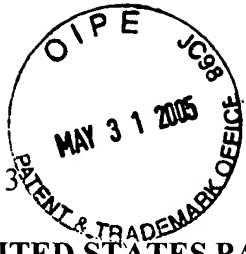


IFW



Docket No.: 066097-0013

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of	:	Customer Number: 20277
Kouichi SAITOU, et al.	:	Confirmation Number: 3766
Application No.: 10/648,236	:	Group Art Unit: 1756
Filed: August 27, 2003	:	Examiner: J. Ruggles
For: PHOTOMASK FOR MANUFACTURING SEMICONDUCTOR DEVICE	:	

RESPONSE TO RESTRICTION REQUIREMENT

Mail Stop Restriction Requirement
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In the Office Action dated May 10, 2005, the Examiner imposed a restriction requirement pursuant to 35 U.S.C. §121, requiring election of one of the following:

- Group I. Claims 1 through 8 and 15, directed to photomasks;
- Group II. Claims 9 through 14, directed to photolithographic methods; or
- Group III. Claims 16 through 18, asserted to be directed to a photographic method unrelated to that of Group II.

In response Applicants elect to prosecute photomask claims 1 through 8 and 15 (Group

I). Favorable consideration of claims 1 through 8 and 15 is solicited.

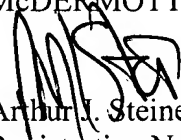
To the extent necessary, a petition for an extension of time under 37 C.F.R. 1.136 is hereby made. Please charge any shortage in fees due in connection with the filing of this paper,

10/648,236

including extension of time fees, to Deposit Account 500417 and please credit any excess fees to such deposit account.

Respectfully submitted,

McDERMOTT WILL & EMERY LLP


Arthur J. Steiner
Registration No. 26,106

600 13th Street, N.W.
Washington, DC 20005-3096
Phone: 202.756.8000 AJS:ntb
Facsimile: 202.756.8087
Date: May 31, 2005

**Please recognize our Customer No. 20277
as our correspondence address.**